P. 1/1 NO. 4833

OCT. 11. 2005 4: 12PM

Service. Thank you.

HOWREY

2941 FAIRVIEW PARK DRIVE SUITES 200 & 300 FALLS CHURCH, VA 22042 PHONE: 703.663.3600 • FAX: 703.336.6950

2005 OCT 12 PH 3: 48

October 11, 2005 Date: Latrice Sims, Office of Finance Name: To: USPTO; Deposit Account Administration/Refunds Company: 571-273-6500 Fax Number: 571-272-6500 Phone Number: Alexandria, VA City: Deborah White Name: From: 4812 User ID: 703-663-3751 Direct Dial No. Charge No: 09101.0502.000000 No. of Pages (including cover): Message: Account No. 012508 - Howrey LLP (Formerly Howrey Simon Arnold & White) Re: Deposit Account Reconciliation Dear Ms. Sims: The item below was charged to the Howrey account in error. I have noted the name and Deposit Account number where the charge should have been debited. Charge Fce Code PTO Posting Ref Docket No. Date 1,170.00 1202 102-0072US-4 09923058 11/15/04 This was filed by Wong Cabello, et al. and should have been deducted from Deposit Account # 501992, PLEASE CREDIT HOWREY ACCOUNT # 012508 2nd request If you have any questions, please contact me. Thank you. The information contained in this transmission is privileged and confidential. It is intended only for the use of the individual or entity named above. If the reader of this message is not the intended recipient, you are hereby notified that any dissembation, distribution or copying of this communication is strictly prohibited. If you

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Date

Signature

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

David Becker et al.

Serial No.: 09/923,058

Filed: August 6, 2001

For: METHODS FOR ENHANCING SILICON

DIOXIDE TO SILICON NITRIDE

SELECTIVITY (AS AMENDED HEREIN)

Group Art Unit: 1763

Examiner: unk

Atty. Dkt. No.: MCRO284-2/LWT

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OF FILM PRELIMINARY AMENDMENT

Assistant Commissioner for Patents Washington, D.C. 20231

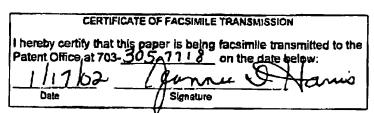
Please consider the enclosed preliminary amendment. Applicant has brought the total number of claims in the application to 94, but only three independent claims are now pending. Hence it is believe that the Applicant owes this office (94 - 20) * \$18.00 = \$ 1,332.00 in connection with this filing. The Assistant Commissioner is authorized to deduct this fee, or any other fees that are due in connection with this response or otherwise, to Deposit Account No. 01-2508/MCRO284--2/LWT.

Reconsideration of the application is respectfully requested.

Adjustment date: 11/30/2005 SDIRETA1 11/15/2004 KBUTLER 00000003 012508 09923058

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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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PRELIMINARY AMENDMENT

Assistant Commissioner for Patents Washington, D.C. 20231

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OF SOLUTION

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Reconsideration of the application is respectfully requested.

I. AMENDMENTS

- Please change the title of the application to the following:
- -- METHODS FOR ENHANCING SILICON DIOXIDE TO SILICON NITRIDE SELECTIVITY ---
 - Please replace the abstract with the following paragraph:
- A process for controlling the <u>plasma</u> etch of a silicon dioxide layer at a high etch rate and high selectivity with respect to silicon nitride, particularly in a multilayer structure, by (1) maintaining various portions of the etch chamber at elevated temperatures, and/or (2) using an etch chemistry having a fluorohydrocarbon gas containing at least as many hydrogen atoms as fluoring atoms, preferably CH₂F₂ or CH₂F. --
- Please replace the specification paragraph beginning at page 1, line 4 with the following paragraph:
- -- This is a continuation application of co-pending U.S. Application Serial Number 09/344.277, filed June 30, 1999, which issued as U.S. Patent Number 6.287,978 on September 11, 2001; which was a continuation of U.S. Applicant Serial Number 08/905,891, filed August 4, 1997, which issued as U.S. Patent Number 6.015,760 on January 18, 2000; which was a continuation of U.S. Application Serial Number 08/152,755, filed November 15, 1993, which issued as U.S. Patent Number 5,880,036 on March 9, 1999; which was a continuation-in-part of U.S. A[a]pplication Serial Number 07/898,505, filed June 15, 1992, which issued as U.S. Patent Number 5,286,344 on February 15, 1994. --

II. REMARKS

Claims 1-29 have been canceled, and new claims 30-123 are pending. The title of the specification has been changed so that it better relates to what applicant is now claiming by virtue of this response. The cross-reference to related applications paragraph has also been updated. Finally, the Abstract has been amended so that that summary better relates to what applicant is now claiming by virtue of this amendment. These amendments do not constitute the addition of new matter, i.e., matter which is not already present in Applicant's specification as filed.

The Examiner is invited to contact the undersigned patent attorney at 713-787-1499 with any questions, comments or suggestions relating to this submission.

Respectfully submitted,

Terril G. Lewis Reg. No. 46,065

Attorney for Applicant

HOWREY SIMON ARNOLD & WHITE,

LLP

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Houston, Texas 77057-2198

Date: 1-17-2002